

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination ONO ET AL.	
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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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X	B	US-5817171	10-1998	Sakurada et al.	117/13
X	C	US-6120598	09-2000	Iida et al.	117/13
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X	N	EP0962557	12-1999	EPO	Iida et al.	C30B 15/00
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NON-PATENT DOCUMENTS

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X	U	Wolf et al., Silicon Processing for the VLSI Era, Volume 1: Process Technology, Lattice Press, Sunset Beach, CA, USA, pp. 8-11, 27-33, 36-72, 124, 139-142, 1986.
V		
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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